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			Application Number	08/824,633
TRANSMITTAL			Filing Date	March 27, 1997
FORM			First Named Inventor	Charles F. Drill, et al.
(to be used for all correspondence after initial filing)			Group Art Unit	3723
			Examiner Name	M. Rachuba
Total Number of Pages in This Submission		7	Attorney Docket Number	PHA 51265B
ENCLOSURES (check all that apply)				
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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Appl. No.

Charles F. Drill, et al.

Appl. No. Filed 08/824,633 March 27, 1997

Title

A Customized Polishing Pad For

Selective Process Performance During Chemical Mechanical

Polishing

Docket No. :

PHA 51265B

NOV 1 8 2002

: 3723

Grp./Art Unit

Examiner: M. Rachuba

TECHNOLOGY CENTER R3700

Assistant Commissioner for Patents Washington DC 20231

## **RESPONSE TO OFFICE ACTION OF 25 SEPTEMBER 2002**

Sir:

## **REMARKS**

This is in response to the Office Action of September 25, 2002. Claims 22-35 are pending and Claims 22-35 have been rejected.

Arguments are presented herein to overcome the rejections set forth in the presently outstanding Office Action of September 25, 2002.

No new matter has been added.

In view of the remarks below, Applicant respectfully requests reconsideration and further examination.

## About The Invention

The present invention relates generally to the field of chemical mechanical polishing, and more particularly to polishing pads that have two or more polishing regions with each polishing region having distinct polishing characteristics which are different from those of the other polishing region(s). These polishing regions, which have different, and distinct, polishing characteristics, are arranged such that a workpiece to be polished, e.g., a wafer, can be selectively frictionally engaged with a particular one of those regions. For example, consistent with the present invention, the